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MEMS, MOEMS, and Micromachining III

Hakan Urey

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Contents

vii *Conference Committee*

SESSION 1 MOEMS DEVICES AND SYSTEMS I

- 6993 02 **NEMS/MEMS cantilever-based biosensors: addressing the open issues (Invited Paper)** [6993-01]
Y. Nemirovsky, A. Shemesh, S. Stolyarova, Technion-Israel Institute of Technology (Israel)
- 6993 03 **Magnetic actuated FR4 scanners for compact spectrometers** [6993-02]
Ç. Ataman, H. Urey, Koç Univ. (Turkey)
- 6993 04 **Micromachined multicavity grey body emitter for the use in MIR spectroscopic systems** [6993-03]
J. Hildenbrand, A. Kürzinger, E. Moretton, Fraunhofer-Institute for Physical Measurement Technique (Germany); A. Greiner, Univ. of Freiburg (Germany); A. Lambrecht, J. Wöllenstein, Fraunhofer-Institute for Physical Measurement Technique (Germany); J. G. Korvink, Univ. of Freiburg (Germany)
- 6993 05 **Optimisation and characterisation of parabolic membrane mirrors** [6993-04]
T. Hellmuth, K. Khrennikov, Hochschule Aalen (Germany); W. Kronast, R. Huster, U. Mescheder, Fachhochschule Furtwangen (Germany)

SESSION 2 MOEMS DEVICES AND SYSTEMS II

- 6993 06 **New technologies for tunable micro-optics (Invited Paper)** [6993-05]
Ch. Friese, A. Werber, F. Krogmann, R. Shaik, W. Mönch, H. Zappe, Univ. of Freiburg (Germany)
- 6993 07 **Fabrication of polymer micro-optical components for integration in silicon MOEMS** [6993-06]
D. Cristea, P. Obreja, M. Kusko, M. Purica, A. Dinescu, National Institute for Research and Development in Microtechnologies (Romania); A. Herrero, Fundación TEKNIKER (Spain); D. Apostol, National Institute for Lasers, Plasma and Radiation Physics (Romania); E. Manea, National Institute for Research and Development in Microtechnologies (Romania)
- 6993 08 **Electrostatically-actuated grating light modulator fabricated using SU-8 photoresist** [6993-07]
T. Aida, Y. Habu, T. Kato, Osaka City Univ. (Japan)

SESSION 3 MICROFABRICATION AND MICROFLUIDICS I

- 6993 0A **Optofluidics and optoelectronic tweezers (Invited Paper)** [6993-10]
A. Jamshidi, A. T. Ohta, J. K. Valley, H.-Y. Hsu, S. L. Neale, M. C. Wu, Univ. of California, Berkeley (USA)

- 6993 0B **Micromachining of InP/InGaAs multiple membrane/airgap structures for tunable optical devices** [6993-11]
T. Kusserow, S. Ferwana, Univ. of Kassel (Germany); T. Nakamura, T. Hayakawa, Canare Electric Co., Ltd. (Japan); N. Dharmarasu, Univ. of Kassel (Germany); B. Vengatesan, Canare Electric Co., Ltd. (Japan); H. Hillmer, Univ. of Kassel (Germany)
- 6993 0C **Vacuum isostatic micro molding of microfluidic structures into polytetrafluoroethylene (PTFE) materials** [6993-12]
T. E. Lizotte, Hitachi Via Mechanics USA Inc. (USA)

SESSION 4 MICROFABRICATION AND MICROFLUIDICS II

- 6993 0D **Technology development for micromirror arrays with high optical fill factor and stable analogue deflection integrated on CMOS substrates (Invited Paper)** [6993-13]
J.-U. Schmidt, M. Friedrichs, Fraunhofer IPMS (Germany); T. Bakke, SINTEF ICT (Norway); B. Voelker, AEMtec GmbH (Germany); D. Rudloff, H. Lakner, Fraunhofer IPMS (Germany)
- 6993 0E **Selective wet etching of AlInN layers for nitride-based MEMS and photonic device structures** [6993-14]
I. M. Watson, C. Xiong, E. Gu, M. D. Dawson, Univ. of Strathclyde (United Kingdom); F. Rizzi, Italian Institute of Technology (Italy); K. Bejtka, P. R. Edwards, R. W. Martin, Univ. of Strathclyde (United Kingdom)
- 6993 0F **Review of production of microfluidic devices: material, manufacturing and metrology** [6993-15]
S. Li, Z. Xu, Singapore-MIT Alliance (Singapore), Nanyang Technological Univ. (Singapore), and Singapore Institute of Manufacturing Technology (Singapore); A. Mazzeo, D. J. Burns, Massachusetts Institute of Technology (USA); G. Fu, Singapore-MIT Alliance (Singapore) and Nanyang Technological Univ. (Singapore); M. Dirckx, V. Shilpiekandula, Massachusetts Institute of Technology (USA); X. Chen, N. C. Nayak, Singapore-MIT Alliance (Singapore) and Nanyang Technological Univ. (Singapore); E. Wong, Massachusetts Institute of Technology (USA); S. F. Yoon, Singapore-MIT Alliance (Singapore) and Nanyang Technological Univ. (Singapore); Z. P. Fang, Singapore Institute of Manufacturing Technology (Singapore); K. Youcef-Toumi, D. Hardt, Massachusetts Institute of Technology (USA); S. B. Tor, C. Y. Yue, Singapore-MIT Alliance (Singapore) and Nanyang Technological Univ. (Singapore); J.-H. Chun, Massachusetts Institute of Technology (USA)

POSTER SESSION

- 6993 0G **Light concentrating micromirror arrays for photovoltaics** [6993-08]
J. Ackermann, O. Setyawati, V. Viereck, N. Dharmarasu, H. Hillmer, Univ. of Kassel (Germany)
- 6993 0H **A microelectromechanical force actuator for nano-tensile testing system** [6993-16]
S. Gao, K. Herrmann, Physikalisch-Technische Bundesanstalt (Germany)

- 6993 0I **Feasibility study for a MEMS modulator suitable for optical system network signalling**
[6993-17]
P. Mitchell, Bookham Technology (United Kingdom); R. G. Jackson, J. K. Luo, Univ. of Bolton
(United Kingdom)
- 6993 0J **Determination of in-plane displacement of MEMS by means of an AFM sensor** [6993-18]
S. Gao, Z. Li, K. Herrmann, Physikalisch-Technische Bundesanstalt (Germany)

Author Index

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- 1 MOEMS Devices and Systems I
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- 2 MOEMS Devices and Systems II
Yael Nemirovsky, Technion-Israel Institute of Technology (Israel)
- 3 Microfabrication and Microfluidics I
Hans Zappe, Albert-Ludwigs-Universität Freiburg (Germany)
- 4 Microfabrication and Microfluidics II
Cağlar Ataman, Koç University (Turkey)

